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Sheet 1 of 1

FORM PTO-1449 REV. 7-98		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. AMAT 5264/5830		SERIAL NO.	
LIST OF CITATIONS BY APPLICANT (Use several sheets if necessary)				APPLICANT Cheng Guo et al.		GROUP 1757	
				FILING DATE October 27, 2000			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
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	AI						
	AJ						
	AK						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	AL						
	AM						
	AN						
	AO						
	AP						
OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)							
SEM	AR	Article entitled "New approach to projection-electron lithography with demonstrated 0.1 um linewidth" by S.D. Berger et al., Applied Physics Letters, 57 (2), July 1990, pages 153-155.					
SEM	AS	Article entitled "Projection electron-beam lithography: A new approach", by S.D. Berger et al., J. Vac. Sci. Technol. B 9 (6), Nov/Dec 1991, pages 2996-2999.					
	AT						
EXAMINER Mohamedulla				DATE CONSIDERED 2/23/02			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							